# Tunable auxetic properties in group-IV monochalcogenide monolayers

Xian Kong,<sup>1</sup> Junkai Deng,<sup>1,\*</sup> Lou Li,<sup>1</sup> Yilun Liu,<sup>2</sup> Xiangdong Ding,<sup>1</sup> Jun Sun,<sup>1</sup> and Jefferson Zhe Liu<sup>3,†</sup>

<sup>1</sup>State Key Laboratory for Mechanical Behavior of Materials, Xi'an Jiaotong University, Xi'an 710049, China

<sup>2</sup>State Key Laboratory for Strength and Vibration of Mechanical Structures, School of Aerospace Engineering, Xi'an Jiaotong University,

Xi'an, China 710049, People's Republic of China

<sup>3</sup>Department of Mechanical Engineering, The University of Melbourne, Parkville VIC 3010, Australia

(Received 1 August 2018; revised manuscript received 23 September 2018; published xxxxx)

Negative Poisson's ratio (NPR) is a counterintuitive material elastic constant that can lead to many unusual auxetic properties. Here, using first-principles calculations, we report tunable negative Poisson's ratio in the outof-plane direction in group-IV monochalcogenide monolayers MX (M = Sn, Ge and X = S, Se). SnSe, GeS, and SnS monolayers have intrinsic NPR  $v_{zx}$  ranging from -0.004 to -0.210 in armchair (x) tension, whereas GeSe monolayer possesses a much larger NPR  $v_{zy}$  of -0.433 in zigzag (y) tension. Our analysis attributes the NPR effects to the relative position of M and X in the puckered structure and the smaller bending stiffness of M-X-M bond angle. We further established the correlation between electronic structures of materials and their crystal structures. It allows us to fine tune GeSe structure via electron doping, leading to a reversible and continuous change of  $v_{zy}$  from -0.821 up to 0.895. We also demonstrate the concept of strain engineering GeSe monolayer to switch its Poisson's ratio  $v_{zx}$  between two different values: 0.583 and -0.433. Our in-depth study provides not only fundamental knowledge but also practical routes for designing 2D smart materials with tunable negative Poisson's ratio, which are desirable for smart devices at small scale.

DOI: 10.1103/PhysRevB.00.004100

2

з

4

5

9

10

11

12

13

14

15

16

17

18

19

20

21

22

23

### I. INTRODUCTION

Poisson's ratio is a fundamental mechanical property of 24 materials, defined as the negative ratio of transverse strain 25 to longitudinal strain under uniaxial tension or compression. 26 Most materials display positive Poisson's ratio ranging from 27 28 0 to 0.5, indicating that when materials are stretched longitudinally, they tend to contract in the transverse direction 29 30 [1,2]. In rare cases, materials have negative Poisson's ratio 31 (NPR), termed as the auxetic effect [3]. They expand rather than contract laterally when stretched in the longitudinal 32 direction. The auxetic effect endows materials with enhanced 33 mechanical properties, including shear resistance [4], inden-34 tation resistance [5], and fracture toughness [6]. As a result, 35 the auxetic materials have been proposed for applications in a 36 broad range of fields, such as medicine, fasteners, tissue en-37 gineering, national security and defense, with more potential 38 applications that will be gradually exploited in the future [7,8]. 39 In the past, the search for the auxetic effect has mainly 40 focused on natural materials and specially designed structures 41 in bulk form. In 1987, NPR behavior was discovered by 42 Lakes in conventional low-density open-cell polymer foams. 43 The key structural feature of these materials is that the ribs 44 of cells permanently protruded inward [9]. Since then, NPR 45 phenomena have been successfully found in many other bulk 46 materials, including some cubic metals [10,11],  $\alpha$ -cristobalite 47 (SiO<sub>2</sub>) [2],  $\alpha$ -TeO<sub>2</sub> [12], the zeolite mineral natrolite [13], 48 hard cyclic hexamers [14], metal-organic frameworks [15], 49

and the folded Miura-ori structure [16,17]. Those auxetic behaviors in bulk materials are mostly attributed to peculiar reentrant or hinged geometric structures.

50

51

52

53

54

55

56

57

58

59

60

61

62

63

64

65

66

67

68

Due to their superior mechanical properties, twodimensional (2D) auxetic materials offer opportunities to design nanoscale devices with specific functionalities and consequently have been subject to intensive research. Recently, the auxetic effect has been reported in several monolayer two-dimensional materials. Theoretical calculations and experiments confirmed that monolayer black phosphorene has an intrinsic auxetic effect [18,19], with a calculated Poisson's ratio of -0.027 in the out-of-plane direction [18]. Few-layer arsenic and borophane were predicted to have out-of-plane NPR as well [20,21]. Moreover, the in-plane NPR has been predicted in graphene [22], rippled graphene [23], two-dimensional silicon dioxide [24], pentagraphene [25,26],  $h\alpha$ -silica [27], Be<sub>5</sub>C<sub>2</sub> [28], and some transition metal dichalcogenides [29]. The NPR effect of 2D materials usually originates from their unique puckered structures.

Most of the reported NPR 2D materials show a nearly 69 invariable Poisson's ratio. Currently, the inability to tune the 70 NPR values in these materials limits their usage in smart 71 electromechanical devices, which have enormous potential for 72 applications in various industrial fields and devices, includ-73 ing medicine, defense, and portable electronic devices. Such 74 limitation could be attributed to the lack of knowledge about 75 the relation between NPR and electronic structures of 2D 76 materials. Indeed, previous studies mostly focused on how the 77 puckered crystal structures affect the NPR [18,23]. Therefore, 78 it is desirable to go one step further to obtain the essential 79 understanding of the influence of electronic structures on NPR 80 effects. That may provide effective ways to tune Poisson's 81

<sup>\*</sup>junkai.deng@mail.xjtu.edu.cn

<sup>&</sup>lt;sup>†</sup>zhe.liu@unimelb.edu.au

ratio via external stimuli, such as charging or electrical field.
Such tunable NPR 2D materials would offer promising opportunities for smart device designs.

In this paper, using first-principles calculations, we find 85 that negative Poisson's ratio generally exists in a set of group-86 IV monochalcogenide monolayers MX (M = Sn, Ge and 87 X = S, Se). SnSe, GeS, and SnS have a negative out-of-plane 88 Poisson's ratio in the armchair (x) tension. In contrast, GeSe 89 has an NPR in the zigzag (y) tension. Our analysis shows that 90 it is an intrinsic property for this type of material. The rela-91 tionship between electronic structures and crystal structures 92 is also established. We propose an effective electron doping 93 method to fine tune the GeSe structure for a reversible and 94 continuous change of  $v_{zy}$  from -0.821 up to 0.895. In the end, 95 we demonstrate the concept of strain engineering to tune the 96 NPR of GeSe monolayer. 97

## **II. METHODS**

Our first-principles calculations were carried out based on 99 the density-functional theory (DFT), as implemented in the 100 Vienna Ab initio Simulation Package (VASP) [30]. Electron ex-101 change and correlation were described using the generalized-102 gradient approximation of the Perdew-Burke-Ernzerhof form 103 [31], and projector-augmented wave potentials were used to 104 treat core and valence electrons [32,33]. The monolayers were 105 placed in the x-y plane. Periodic boundary condition was 106 applied in all three directions. The cell has a length of 20 Å 107 in the z direction to avoid the interactions between adjacent 108 layers. To hold this interlayer space constant, the VASP source 109 code was modified to allow the cells to relax within the x-y110 basal plane only. In all cases, the atoms were relaxed freely 111 in all directions. An energy cutoff of 600 eV was chosen for 112 the plane-wave basis set. All of the atoms in the unit cell 113 were fully relaxed until the force on each atom was less than 114  $0.001 \text{ eV}/\text{\AA}$ , ensuring the accuracy for the optimization of the 115 structure. We have tested to ensure that the selected cutoff 116 energy was sufficiently large for a well converged lattice 117 constant value. 118

119

98

### **III. RESULTS AND DISCUSSION**

The relaxed crystal structures of four group-IV 120 monochalcogenide MX monolayers are shown in Fig. 1. 121 All materials have puckered honeycomblike lattice similar 122 to black phosphorene [34]. However, for SnS, SnSe, and 123 GeS, the *M* atoms are located at the outmost layer of the 124 puckered structure, while for GeSe, the outmost layer is 125 occupied by the X atoms. We will show later that this subtle 126 structural difference has a significant effect on Poisson's ratio 127 of group-IV monochalcogenides. The armchair direction 128 and zigzag direction of the lattice are defined as x and y129 coordinates, respectively. Unlike black phosphorene that only 130 contains two atomic layers, each group-IV monochalcogenide 131 monolayer MX contains four atomic layers stacked in 132 the z direction, including two M atomic layers and two 133 X atomic layers. Each M atom is covalently bonded to 134 three neighboring X atoms and vice versa. The geometric 135 anisotropy implies that these materials exhibit different 136 mechanical response being subject to uniaxial loading in 137

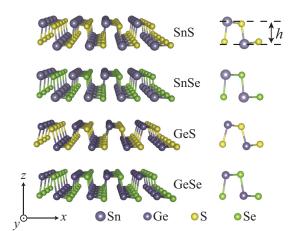


FIG. 1. Crystal structures of group-IV monochalcogenide (MX) monolayers. The atoms are distributed on four atomic layers. The thickness of these monolayers is defined as the vertical distance between the top and the bottom layers. From the side view, for SnS, SnSe, and GeS, group-IV atoms (M) are on the two outer layers, whereas for GeSe, chalcogen atoms (X) are on the two outer layers.

the x direction or the y direction. For a monolayer, the translational symmetry along the z direction is absent. We thus define the thickness of these materials as the vertical distance between the top and the bottom atomic layers. 141

Next, we examine the structural response under uniaxial 142 strain along the x or y direction and then calculate Poisson's 143 ratios. Poisson's ratio is defined by  $v_{ij} = -\partial \varepsilon_i / \partial \varepsilon_j$ , where  $\varepsilon_i$ 144 is the uniaxial strain applied in the j axis and  $\varepsilon_i$  is the resulting 145 strain along the *i* axis. Figure 2 shows resulting strains in the 146 two transverse directions under a uniaxial strain  $\varepsilon_x$  or  $\varepsilon_y$  in 147 the range from -2% to 2%. Such a strain range is feasible 148 in typical experimental measurements on 2D materials [35]. 149 Good linear correlations are observed, and materials show 150 NPR in the out-of-plane direction. In Fig. 2, for SnS, SnSe, 151 and GeS, under stretching in the x direction, their  $\varepsilon_z$  values 152 remain positive and increase with increasing  $\varepsilon_x$ , indicating 153 thickness enhancement. Thus, they have negative Poisson's 154 ratios  $v_{zx}$ . The similar relation is observed for GeSe but under 155 uniaxial strain in the y direction. It has a negative  $v_{zy}$  which is 156 analogous to black phosphorene [18]. In addition, we find that 157 in-plane Poisson's ratios  $v_{xy}$  and  $v_{yx}$  are all positive (Fig. 2). 158

Table I summarizes our results for calculated Poisson's ratios. Although the monochalcogenide monolayers possess similar structures to black phosphorene, the magnitudes of their NPR values are much higher than that of black phosphorene (-0.027) [18]. This reveals that they can have 163

TABLE I. Poisson's ratio results of group-IV monochalcogenide monolayers.

Materials	$v_{zx}$	$v_{zy}$	$v_{yx}$	$v_{xy}$
SnS	-0.004	0.404	0.422	0.961
SnSe	-0.210	0.352	0.423	0.851
GeS	-0.208	0.411	0.420	1.401
GeSe	0.583	-0.433	0.391	1.039

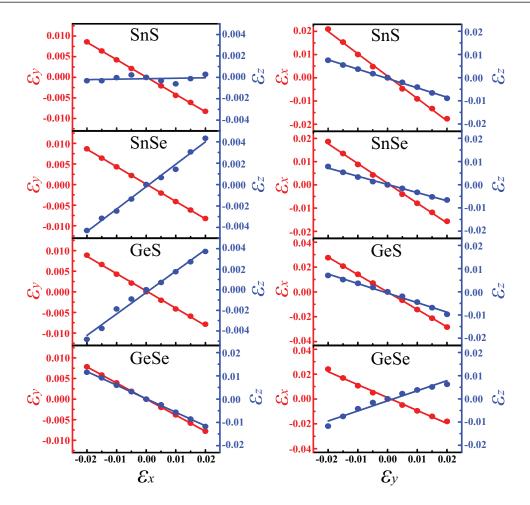


FIG. 2. The correlations between applied strain along the x(y) direction and two resultant transverse strains along the y(x) or z direction.

more sensitive thickness response under in-plane deformation. 164 Particularly, GeSe monolayer has more significant out-of-165 plane NPR  $\nu_{zv} \sim -0.433$ . To our knowledge, it is the largest 166 intrinsic NPR value among known pristine 2D materials 167 [18,20-22,24,25,28,29,36-38]. Besides, in-plane positive 168 Poisson's ratios  $v_{xy}$  for these monochalcogenide monolayers 169 are also larger than usual (0.5). That could be because they 170 are very soft along the armchair direction due to the hingelike 171 structure. Interestingly, GeSe and GeS have in-plane positive 172 Poisson's ratios  $v_{xy}$  even larger than 1. Gomes *et al.* reported 173 a similar in-plane positive Poisson's ratio  $v_{xy}$  for GeS [38]. 174 It means that the transverse response strain  $\varepsilon_x$  has a larger 175 magnitude than the applied longitudinal strain  $\varepsilon_v$  (Fig. 2). 176 This property may have applications in strain amplifiers for 177 functional nanodevices [39-43]. 178

To understand the origins of the NPR of group-IV 179 monochalcogenide monolayers, we examine the change of 180 their crystal structures under uniaxial strain  $\varepsilon_x$  or  $\varepsilon_y$ . In 181 Fig. 3(a), the black lines and red lines represent the variation 182 of z coordinates of group-IV elements (M) and chalcogens 183 (X) at the top two atomic layers respectively, under strain 184 ranging from -0.02 to 0.02. The basis point (z = 0) is se-185 lected as the middle height of the monolayer. The black and 186 red arrows in Fig. 3(b) depict the direction of motion for 187 the X and M atoms under tensile strains of  $\varepsilon_x$  or  $\varepsilon_y$ . When 188 the monolayers are stretched in the x direction, it is clear 189

that the M atoms always move outward, while the X atoms 190 move inward. The opposite directions of motion of the X191 and M atoms are characteristic of hingelike structures and 192 can be explained as follows: it is well known that group-IV 193 element materials are much stiffer than chalcogen materials 194 [44]. Therefore, the change in the bond angle M-X-M is 195 more significant under stretching along the x direction. As 196 a result, the X atoms show an inward movement and the M197 atoms show an outward movement. When the monolayers 198 are stretched in the y direction, it is equivalent to the lateral 199 contraction in the x direction due to in-plane Poisson's effect 200 as shown in Fig. 3(b). Consequently, the directions of motion 201 of the *M* atoms and *X* atoms are reversed, i.e., the *M* atoms 202 move inward and the X atoms move outward. 203

One can infer from Fig. 3(a) that for SnS, SnSe, and GeS 204 monolayers, the M atoms are located at the two outmost 205 atomic layers, since the z coordinates of the M atoms (black 206 symbols) is larger than those of the X atoms (red symbols). 207 The motion of the M atoms determines the change of thick-208 ness. As shown in Fig. 3(b), when stretched along the x 209 direction, the M atoms move outward, leading to increasing 210  $\varepsilon_{7}$  and thus a negative Poisson's ratio  $v_{7x}$ . When stretched 211 along the y direction, the M atoms move inward, leading to 212 decreasing  $\varepsilon_z$  and thus a positive Poisson's ratio  $v_{zy}$ . However, 213 GeSe monolayer shows a distinctive structural feature, i.e., 214 the X (Se) atom located at the two outmost atomic layers. 215

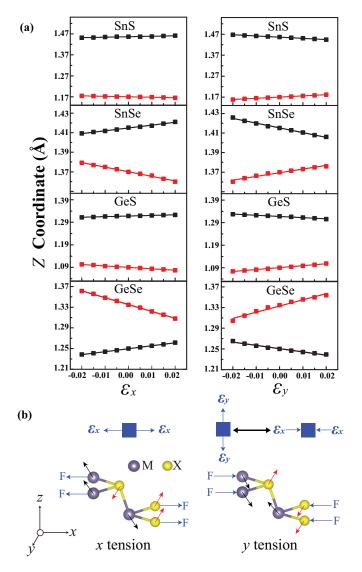


FIG. 3. (a) The motion of two atoms in the top two atomic layers under the strains in x or y direction. The black curves represent the z coordinates change of group-IV elements, and red curves represent the z coordinates change of chalcogens. The basis point (zero in z coordinates) is selected at the middle height of puckered crystal structures. (b) The black and red arrows depict the motion direction of the M and X atoms under tensile strains of  $\varepsilon_x$  or  $\varepsilon_y$ . The blue boxes show the strain conditions of these 2D materials. Note that stretching along the y direction is equivalent to contraction along the x direction because of Poisson's effect.

Therefore, GeSe shows the opposite sign of Poisson's ratiocompared with the other three materials.

In order to explore the mechanism of the structural differ-218 ences between GeSe and other MX monolayers, we analyze 219 electronic structures of MX monolayers. As a prototypical 220 example, Fig. 4(a) shows the projected electron density of 221 states (PDOS) of GeS versus  $E - E_f$ , where  $E_f$  denotes 222 Fermi level. Below -1.4 eV, DOS peaks for s orbitals and 223 p orbitals show clear overlaps. Via inspection of the de-224 composed charge density, the overlaps stem from the cova-225 lent bonds connecting the M (Ge) and X (S) atoms. The 226 electron-density distributions of GeS in the energy range from 227

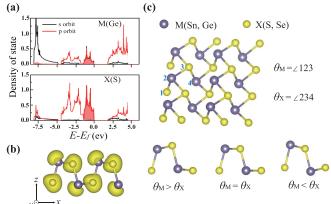


FIG. 4. (a) Projected electronic density of states (PDOS) for MX (GeS) from DFT calculation. The analysis in main text suggests that the M and X atoms undergo  $sp^3$  hybridization. For each atom, three of the half-filled  $sp^3$  orbitals form the covalent bonds connecting the M and X atoms. For both M and X, there is a lone-pair orbital (the shaded region). (b) Charge density of the lone-pair orbital on MX (GeS). The size of the lone-pair orbitals affects the tetrahedral bond angle  $\theta_M$  and  $\theta_X$ . (c) The relative magnitude of  $\theta_M$  and  $\theta_X$  leads to the three different puckered structures.

-1.4 to 0 eV are shown in Fig. 4(b). They appear like lone-228 pair orbitals. For the M (Ge) atom, it is s-p hybridization 229 lone-pair orbital; for the X (S) atom, it is *p*-type lone-pair 230 orbital. We can conclude that every M (Ge) and X (S) atom 231 form three covalent bonds with its nearest-neighbor atoms and 232 there is also a lone pair orbital for each atom. Figures 4(b) and 233 4(c) show that the three covalent bonds and lone pair orbital 234 form a tetrahedral structure, suggesting a  $sp^3$ -like atomic 235 orbital hybridization for Ge and S atoms. 236

As shown in Fig. 4(c), we have defined two bond angles 237  $\theta_M$  and  $\theta_X$ . These two bond angles should depend on the 238 electronic structure, particularly the lone-pair electrons. For 239 either group-IV or chalcogen atoms, moving down the peri-240 odic table, the lone-pair electron cloud will be more spread 241 in space. It would force the three covalent bonds to bend 242 downward, leading to smaller bond angles. This is consistent 243 with our calculated angle values in MX crystals listed in 244 Table II. Ge has a bond angle  $\theta_{Ge}$  of 94–97°, whereas Sn has 245 a bond angle  $\theta_{Sn}$  within 89–92°. S has a bond angle  $\theta_S$  of 246 101–105°, whereas Se has a smaller angle  $\theta_{Se}$  about 94°. The 247 difference between the bond angles of the M and X atoms 248 is also noticeable. Generally, the X atoms have a larger bond 249 angle than the *M* atoms ( $\theta_X > \theta_M$ ). This could be attributed 250 to its *p*-orbital-like lone pair. For example, compared with Ge 251

TABLE II. The tetrahedral angle  $\theta_M$  and  $\theta_X$  (Fig. 4) of the four MX crystals.

Materials	$\theta_X$ (degree)	$\theta_M$ (degree)
SnS	101.09	89.14
SnSe	94.22	92.44
GeS	105.18	94.74
GeSe	93.82	97.44

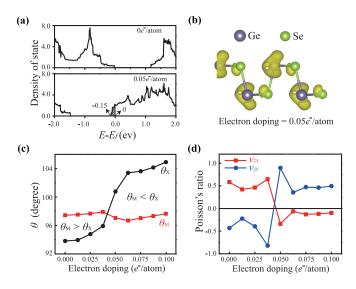


FIG. 5. Tunable Poisson's ratio of monolayer GeSe via electron doping engineering. (a) DOS (density of states) of GeSe with zero and  $0.050e^{-}$ /atom electron doping, respectively. The shaded region shows that the excess electrons located at the energy levels ranging from -0.15 to 0 eV (relative to Fermi level), which corresponds to the range from LUMO to LUMO + 0.15 eV in the zero electron doping case. (b) The distribution of doped excess electrons. (c) Electron doping leads to almost constant of  $\theta_M$  and significant increase of  $\theta_X$ . The crossover takes places at about  $0.040e^{-}$ /atom. (d) Poisson's ratio  $v_{zx}$  ( $v_{zy}$ ) as a function of electron doping. They change sign from positive (negative) into negative (positive) arising from the crossover of the two angles in (c). See details in main text.

atoms, the lone-pair electrons are more uniformly distributed around S atoms [Fig. 4(b)]. There is less repulsion to push down the covalent bonds. But, if we choose an *M* atom in a top row and choose an *X* atom in a down row in the periodic table, the  $\theta_X$  and  $\theta_M$  could be comparable, e.g., GeSe, whose  $\theta_X$  value can be smaller than  $\theta_M$ .

Based on the comparison of  $\theta_M$  and  $\theta_X$  values, we have 258 three different cases as illustrated in Fig. 4(c). Case I has  $\theta_M >$ 259  $\theta_X$ , where smaller  $\theta_X$  causes the X atom located at the outmost 260 atomic layers, e.g., GeSe. Case II ( $\theta_M = \theta_X$ ) corresponds to 261 a critical case where the X and M atoms are located on the 262 same plane. The black phosphorene belongs to this case. Case 263 III ( $\theta_M < \theta_X$ ) corresponds to the other three materials, where 264 smaller  $\theta_M$  causes the M atoms to be located at the outmost 265 atomic layers. 266

It should be noted that the physical origin of black phos-267 phorene's NPR is different from the four materials in this 268 paper. Its two bond angles remain equivalent even under 269 strain conditions. That is because the two bond angles in 270 phosphorene are constrained by chemical symmetry. There-271 fore, phosphorene can be regarded as a re-entrant structure 272 involving two coupled orthogonal hinges [18]. This might be 273 the reason for its relatively small NPR value (-0.027). 274

Our in-depth analysis of the electronic structure of MXshows that lone pair electrons play an essential role in the subtle difference between GeSe and other MX structures. For MX, both HOMO (highest occupied molecular orbital) and LUMO (lowest unoccupied molecular orbital) levels represent

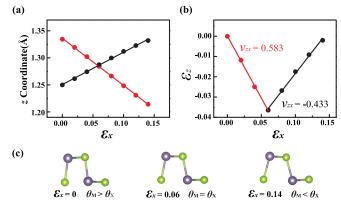


FIG. 6. Tunable Poisson's ratio  $v_{zx}$  of monolayer GeSe via strain engineering in the x direction. (a) The z coordinates change of atom Ge (black line) and atom Se (red line), suggesting that the z coordinates of two atoms on the top two layers will be the same at  $\varepsilon_x = 6\%$ . (b) The transverse strain  $\varepsilon_z$  when GeSe is subjected to a strain  $\varepsilon_x$  in the range from 0 to 0.14. Poisson's ratio  $v_{zx}$  changes from a positive value 0.583 to a negative value -0.433. (c) Cartoons to show the structural change of GeSe under different  $\varepsilon_x$  strains. There is a transition at  $\varepsilon_x = 6\%$ , corresponding to the intersection point of two lines in (a). The competition of bond angles  $\theta_M$  and  $\theta_X$ determines the sign of Poisson's ratio. See details in main text.

lone pair orbitals. It thus inspires us to propose electron dop-280 ing as an effective way to tune the crystal structure and thus 281 Poisson's ratio. Figure 5(a) shows the density of states (DOS) 282 curves for GeSe monolayer with zero and  $0.050e^{-1}$ /atom 283 electrons doping, respectively. The excess doped electrons 284 are occupied within the energy level ranging from -0.15 to 285 0 eV (Fermi level). This region corresponds to energy levels 286 from LUMO to LUMO + 0.15 eV in the charge neutral case. 287 The distribution of excess electrons is presented in Fig. 5(b), 288 showing lone pair orbital features. Similar to Fig. 4, the doped 289 electrons distribute around Ge atoms mostly in a region away 290 from the three covalent bonds, whereas the distribution around 291 the Se atom is more spherical with the highest density within 292 the tetrahedron enclosed by the three covalent bonds. The 293 different distributions around Ge and Se atoms (arising from 294 their lone pair orbital differences in Fig. 4) should lead to 295 different changes in the bond angles. As shown in Fig. 5(c), 296 while the angle  $\theta_M$  remains almost the same, the angle  $\theta_X$ 297 increases significantly upon electron doping. When the doped 298 electron concentration exceeds 0.040  $e^{-}/atom$ ,  $\theta_X$  becomes 299 larger than  $\theta_M$ . Consequently, as shown in Fig. 5(d), Poisson's 300 ratio  $v_{zx}$  ( $v_{zy}$ ) changes from a positive (negative) into a neg-301 ative (positive) value. The tuning range of Poisson's ratio  $v_{7v}$ 302 is very large, from -0.821 to 0.895. Note that the maximum 303 doping level of 0.100  $e^{-}$ /atom corresponds to the area density of 2.35 × 10<sup>14</sup> $e^{-}$  cm<sup>-2</sup>, which is feasible in the experiments 304 305 [45]. 306

In addition to electron doping, we find strain engineering as another effective way to alter Poisson's ratio for GeSe monolayer. When stretching it along the *x* direction, the Se atoms move inward and Ge atoms move outward (Fig. 3). The thickness of GeSe reduces at small  $\varepsilon_x$  value thus showing a positive Poisson's ratio  $v_{zx}$ . Further stretching along the *x* 312

direction to a critical point, the Se and Ge atoms would sit at 313 the same atomic layer. Beyond this point, the Ge atoms are 314 displaced to the outmost atomic layer. The outward motion 315 of the Ge atoms then increases the thickness, leading to a 316 negative Poisson's ratio  $v_{zx}$ . Our DFT calculations verified our 317 expectation. Figure 6(a) shows the change of z coordinates for 318 the Ge atom and Se atom when GeSe is subject to uniaxial 319 strain  $\varepsilon_r$  from 0 to 0.14. It is clear that the two lines meet at 320  $\varepsilon_x = 0.06$ . At this critical point, the Ge and Se atoms are on 321 the same atomic plane. Poisson's ratio  $v_{zx}$  exhibits a sudden 322 change from 0.583 to -0.433 in Fig. 6(b). The structural 323 distortion under  $\varepsilon_x$  is shown in Fig. 6(c). The competition 324 between  $\theta_M$  and  $\theta_X$  determines the sign of Poisson ratio. We 325 believe it is a general concept to tailor Poisson's ratio of these 326 group-IV monochalcogenide monolayers through applying 327 strain along a specific direction. Most interestingly, the group-328 IV monochalcogenides monolayers are known as piezoelec-329 tric 2D materials. Their giant in-plane piezoelectricity along 330 the x direction suggests that the external electric fields can 331 lead to tensile strains for group-IV monochalcogenides mono-332 layers, thus changing Poisson's ratio [46]. 333

334

## **IV. CONCLUSION**

In summary, our DFT calculations demonstrate that group IV monochalcogenide monolayers (SnS, SnSe, GeS, GeSe)
generally have negative out-of-plane Poisson's ratio. The rel-

352

ative magnitudes of tetrahedra covalent bond angles  $\theta_M$  and 338  $\theta_X$  (for the *M* and *X* atoms respectively) determine either a 339 *M* or *X* atom sitting at the outmost atomic layer. Then we can 340 obtain either negative Poisson's ratio  $v_{zx}$  or  $v_{zy}$ , demonstrating 341 the intrinsic auxetic property of group-IV monochalcogenide 342 monolayers. Through the in-depth analysis of electronic struc-343 tures, we further establish its relation to the crystal structure 344 and demonstrate that doping electrons can effectively tune 345 Poisson's ratio  $v_{zv}$  of GeSe monolayer in a wide range from 346 -0.821 to 0.895. We also propose to use strain engineering to 347 tune Poisson's ratio of GeSe monolayer between two different 348 values: 0.583 and -0.433. Such a tunable NPR 2D material 349 would provide more design options and concepts in smart 350 devices at small scale. 351

#### ACKNOWLEDGMENTS

The authors gratefully acknowledge the support of NSFC 353 (Grants No. 51728203, No. 51471126, No. 51320105014, 354 No. 51621063) and the support by 111 project 2.0 (Grant 355 No. BP2018008). J.D. also thanks the support of the China 356 Postdoctoral Science Foundation (Grant No. 2016T90911) 357 and the Fundamental Research Funds for the Central Univer-358 sities. J.Z.L. acknowledges the support from ARC discovery 359 projects and HPC from National Computational Infrastructure 360 from Australia. This work was also supported by State Key 361 Laboratory for Mechanical Behavior of Materials and HPC 362 platform of Xi'an Jiaotong University. 363

- M. D. Biegalski, K. Dörr, D. H. Kim, and H. M. Christen, Appl. Phys. Lett. 96, 151905 (2010).
- [2] A. Yeganeh-Haeri, D. J. Weidner, and J. B. Parise, Science 257, 650 (1992).
- [3] K. E. Evans, M. A. Nkansah, I. J. Hutchinson, and S. C. Rogers, Nature (London) 353, 124 (1991).
- [4] J. B. Choi and R. S. Lakes, J. Mater. Sci. 27, 5375 (1992).
- [5] R. S. Lakes and K. Elms, J. Compos. Mater. 27, 1193 (1993).
- [6] J. B. Choi and R. S. Lakes, Int. J. Fract. 80, 73 (1996).
- [7] F. Scarpa, IEEE Signal Process. Mag. 25, 128 (2008).
- [8] Y. J. Park and J. K. Kim, Adv. Mater. Sci. Eng. 2013, 853289 (2013).
- [9] R. Lakes, Science 235, 1038 (1987).
- [10] F. Milstein and K. Huang, Phys. Rev. B 19, 2030 (1979).
- [11] R. H. Baughman, J. M. Shacklette, A. A. Zakhidov, and S. Stafström, Nature (London) 392, 362 (1998).
- [12] H. Ogi, M. Fukunaga, M. Hirao, and H. Ledbetter, Phys. Rev. B 69, 024104 (2004).
- [13] J. J. Williams, C. W. Smith, K. E. Evans, Z. A. D. Lethbridge, and R. I. Walton, Chem. Mater. **19**, 2423 (2007).
- [14] K. W. Wojciechowski, Mol. Phys. 61, 1247 (1987).
- [15] A. U. Ortiz, A. Boutin, A. H. Fuchs, and F. X. Coudert, Phys. Rev. Lett. **109**, 195502 (2012).
- [16] Z. Y. Wei, Z. V. Guo, L. Dudte, H. Y. Liang, and L. Mahadevan, Phys. Rev. Lett. **110**, 215501 (2013).
- [17] J. L. Silverberg, A. A. Evans, L. McLeod, R. C. Hayward, T. Hull, C. D. Santangelo, and I. Cohen, Science 345, 647 (2014).
- [18] J. W. Jiang and H. S. Park, Nat. Commun. 5, 4727 (2014).

- [19] Y. Du, J. Maassen, W. Wu, Z. Luo, X. Xu, and P. D. Ye, Nano Lett. 16, 6701 (2016).
- [20] H. Jianwei, X. Jiafeng, Z. Zhiya, Y. Dezheng, S. Mingsu, and X. Desheng, Appl. Phys. Express 8, 041801 (2015).
- [21] L. Kou, Y. Ma, C. Tang, Z. Sun, A. Du, and C. Chen, Nano Lett. 16, 7910 (2016).
- [22] J. W. Jiang, T. Chang, X. Guo, and H. S. Park, Nano Lett. 16, 5286 (2016).
- [23] H. Qin, Y. Sun, J. Z. Liu, M. Li, and Y. Liu, Nanoscale 9, 4135 (2017).
- [24] Z. Gao, X. Dong, N. Li, and J. Ren, Nano Lett. 17, 772 (2017).
- [25] H. Sun, S. Mukherjee, and C. V. Singh, Phys. Chem. Chem. Phys. 18, 26736 (2016).
- [26] S. Zhang, J. Zhou, Q. Wang, X. Chen, Y. Kawazoe, and P. Jena, Proc. Natl. Acad. Sci. U.S.A. 112, 2372 (2015).
- [27] V. O. Ozcelik, S. Cahangirov, and S. Ciraci, Phys. Rev. Lett. 112, 246803 (2014).
- [28] Y. Wang, F. Li, Y. Li, and Z. Chen, Nat. Commun. 7, 11488 (2016).
- [29] L. Yu, Q. Yan, and A. Ruzsinszky, Nat. Commun. 8, 15224 (2017).
- [30] G. Kresse and J. Furthmüller, Phys. Rev. B 54, 11169 (1996).
- [31] J. P. Perdew, K. Burke, and M. Ernzerhof, Phys. Rev. Lett. 77, 3865 (1996).
- [32] G. Kresse and D. Joubert, Phys. Rev. B 59, 1758 (1999).
- [33] P. E. Blöchl, Phys. Rev. B 50, 17953 (1994).
- [34] L. Kou, C. Chen, and S. C. Smith, J. Phys. Chem. Lett. 6, 2794 (2015).

- [35] P. Li, C. Jiang, S. Xu, Y. Zhuang, L. Gao, A. Hu, H. Wang, and Y. Lu, Nanoscale 9, 9119 (2017).
- [36] L. C. Zhang, G. Qin, W. Z. Fang, H. J. Cui, Q. R. Zheng, Q. B. Yan, and G. Su, Sci. Rep. 6, 19830 (2016).
- [37] S. Woo, H. C. Park, and Y.-W. Son, Phys. Rev. B 93, 075420 (2016).
- [38] L. C. Gomes, A. Carvalho, and A. H. Castro Neto, Phys. Rev. B 92, 214103 (2015).
- [39] Y. Huang, J. Liang, and Y. Chen, J. Mater. Chem. 22, 3671 (2012).
- [40] X. Yu, H. Cheng, M. Zhang, Y. Zhao, L. Qu, and G. Shi, Nat. Rev. Mater. 2, 17046 (2017).

- [41] H. Cheng, Y. Huang, G. Shi, L. Jiang, and L. Qu, Acc. Chem. Res. 50, 1663 (2017).
- [42] Z. Chang, J. Deng, G. G. Chandrakumara, W. Yan, and J. Z. Liu, Nat. Commun. 7, 11972 (2016).
- [43] J. Deng, Z. Chang, T. Zhao, X. Ding, J. Sun, and J. Z. Liu, J. Am. Chem. Soc. 138, 4772 (2016).
- [44] C. Kittel, *Introduction to Solid State Physics* (John Wiley and Sons, New York, 1986), p. 57, Table 3.
- [45] D. K. Efetov and P. Kim, Phys. Rev. Lett. **105**, 256805 (2010).
- [46] R. Fei, W. Li, J. Li, and L. Yang, Appl. Phys. Lett. 107, 173104 (2015).